

an article comprising:

a window electrode proximal a wall of said chamber, said antenna and wall being positioned adjacently, said window electrode being operable as:

(a) a capacitive electrode accepting RF power to capacitively couple plasma source power into the chamber, and

AB (b) a window electrode passing RF power therethrough from said antenna into said chamber to inductively couple plasma source power into the chamber.

Please amend claim 19 as follows:

19. (Once Amended) A plasma reactor comprising:

a plasma reactor chamber enclosed by a vacuum enclosure wall and a workpiece support for holding a workpiece within the interior of said chamber during processing, and a window electrode facing the interior of said chamber, said window electrode forming a portion of said vacuum enclosure wall;

AB an inductive plasma source power applicator overlying said window electrode;

at least one RF plasma source power supply;
said reactor being operable in each one of two modes, said modes comprising:

(a) a capacitively coupled plasma mode wherein said RF plasma source power supply is coupled to said window electrode, and

(b) an inductively coupled plasma mode wherein said RF plasma source power supply is coupled to said inductive power applicator instead of said window electrode.

Please add the following claim:

27. (New) The reactor of Claim 13 wherein said plasma reactor chamber comprises a vacuum enclosure wall, and said window electrode comprises a section of said wall that is adjacent said inductive source power applicator.